

	Hits	Search Text	DBs	Time Stamp
1	10	("6156674" "6281100" "6291363" "6380611" "6383723").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:43
2	2	"6780728".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:43
3	2	"20040265746"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:43
4	40	("4086074" "4622735" "4683645" "4766090" "5099304" "5236865" "5444024" "5470784" "5670298" "6037239" "6096621" "6130140" "6133105" "6133116" "6177235" "6277709" "6277728" "6440793" "6465325" "6720638").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:46
5	2	"20010006759"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:46
6	2	"20020076879"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:46
7	2	"20020196651"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:46
8	2	"20030013272"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:48

	Hits	Search Text	DBs	Time Stamp
9	12	("3349474" "5904517" "5998264" "6180465" "6207485" "6548854").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:48
10	2	"20030045060"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:49
11	2	"20030045078"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:49
12	4	("6753618" "5470794").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50
13	2	"20030219942"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50
14	2	"20040245560"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50
15	5	"2004024559"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50
16	2	"20040046197"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50
17	2	"20040043228"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50

	Hits	Search Text	DBs	Time Stamp
18	2	"20030213987"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:50
19	2	"20030205729"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 14:51
20	132	photoresist and substrate and (treat treating treated) with basic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:23
21	0	S1 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
22	0	S2 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
23	0	S3 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
24	0	S4 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
25	0	S5 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
26	0	S6 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21

	Hits	Search Text	DBs	Time Stamp
27	0	S7 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
28	0	S8 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
29	0	S10 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
30	0	S11 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:21
31	0	S12 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
32	0	S13 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
33	0	S14 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
34	0	S15 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
35	0	S16 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22

	Hits	Search Text	DBs	Time Stamp
36	0	S17 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
37	0	S18 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
38	0	S19 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
39	0	S20 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
40	0	S9 and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:22
41	57	photoresist and substrate same (treat treating treated) with basic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:26
42	0	positive adj photoresist and substrate same (treat treating treated) with basic and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:24
43	7	positive adj photoresist and substrate same (treat treating treated) with basic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:24
44	43	photoresist and substrate with (treat treating treated) with basic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:58

	Hits	Search Text	DBs	Time Stamp
45	1	photoresist and substrate same (treat treating treated) with basic and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:27
46	1	photoresist and substrate with (treat treating treated) with basic and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:27
47	4	photoresist and substrate and (treat treating treated) with basic and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:43
48	0	(S1 S2 S3 S4 S5 S6 S7 S8 S9 S10 S11 S12 S13 S14 S15 S16 S17 S18 S19 S20) and photoresist and substrate and (treat treating treated) with basic and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:31
49	41	(S1 S2 S3 S4 S5 S6 S7 S8 S9 S10 S11 S12 S13 S14 S15 S16 S17 S18 S19 S20) and photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:32
50	5	(S1 S2 S3 S4 S5 S6 S7 S8 S9 S10 S11 S12 S13 S14 S15 S16 S17 S18 S19 S20) and photoresist and basic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:31
51	6	(S1 S2 S3 S4 S5 S6 S7 S8 S9 S10 S11 S12 S13 S14 S15 S16 S17 S18 S19 S20) and photoresist and (treat treating treated)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/16 15:32
52	146	photoresist and substrate and (treat treating treated) with fluoride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:44
53	21	photoresist and substrate and (treat treating treated) with tetramethyl	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:53

	Hits	Search Text	DBs	Time Stamp
54	918	photoresist and substrate and (treat treating treated) same temperature same pressure	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:45
55	222	photoresist and substrate and (treat treating treated) same temperature same pressure same (room ambient)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:45
56	5	photoresist and substrate and (treat treating treated) same temperature near2 (room abient) same pressure near2 (room ambient)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:46
57	35	photoresist and substrate and (treat treating treated) with ammonium adj fluoride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:49
58	22	photoresist and substrate and (substrate surface) with (treat treating treated) with ammonium adj fluoride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:50
59	3	photoresist and substrate and (substrate surface) with (treat treating treated) with ammonium adj fluoride same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:50
60	10	photoresist and substrate and (treat treating treated) with ammonium adj fluoride same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:51
61	9	photoresist and substrate and (treat treating treated) with tetramethyl same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:55
62	11	photoresist and substrate and (treat treating treated) with tetramethyl with (substrate surface)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:56

	Hits	Search Text	DBs	Time Stamp
63	5	photoresist and substrate and (treat treating treated) with tetramethyl with (substrate surface) same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:56
64	68	photoresist and (surface substrate) with (treat treating treated) with basic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:59
65	0	photoresist and (surface substrate) with (treat treating treated) with basic same tetramethyl	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:59
66	0	photoresist and (surface substrate) with (treat treating treated) with basic same ammonium adj fluoride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 17:00
67	0	photoresist and (surface substrate) same (treat treating treated) with basic same tetramethyl	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 16:59
68	0	photoresist and (surface substrate) same (treat treating treated) with basic same ammonium adj fluoride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/17 17:00
69	2325	430/313.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:23
70	929	430/327.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:28
71	156	438/765.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:28

	Hits	Search Text	DBs	Time Stamp
72	249	438/769.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:29
73	166	438/952.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:29
74	186	438/942.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:29
75	235	438/947.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:29
76	162	438/948.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:29
77	370	438/949.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:30
78	1567	438/780.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:30
79	467	438/781.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:31
80	355	438/798.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:32

	Hits	Search Text	DBs	Time Stamp
81	33	438/497.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/02/18 13:32
82	3734	tetramethyl adj ammonium adj hydroxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 18:08
83	1343	tetramethyl adj ammonium adj hydroxide and substrate and photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 17:46
84	161	tetramethyl adj ammonium adj hydroxide and substrate and photoresist and antireflective	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 17:47
85	2151	tetramethyl adj ammonium adj hydroxide same antireflective substrate and photoresist and antireflective	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 17:47
86	47	tetramethyl adj ammonium adj hydroxide same antireflective and substrate and photoresist and antireflective	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 17:50
87	47	tetramethyl adj ammonium adj hydroxide same antireflective and substrate and photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 17:51
88	4	tetramethyl adj ammonium adj hydroxide with antireflective and substrate and photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 17:51
89	10483	ammonium adj fluoride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 18:08

	Hits	Search Text	DBs	Time Stamp
90	1350	ammonium adj fluoride and substrate and photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 18:08
91	35	ammonium adj fluoride and substrate and photoresist and antireflective	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 18:09
92	4	ammonium adj fluoride same antireflective and substrate and photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/03/03 18:09